

REFLECTIVE MASK BLANK, AND METHOD FOR MANUFACTURING THEREOF

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ABSTRACT

Metal and metalloid elements for an absorber film of a reflective mask blank are selected from first, second and third elements included in first, second and third regions, respectively, that are defined by a refractive index n and an extinction coefficient k of a
10 simple substance of each of the metal and metalloid elements, and the absorber film is formed so as to have a reflectance ratio of 0.05 to 0.25, and a phase shift of 180 to 260° by the selected metal and metalloid elements.

[Figure 5]